

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
18 October 2001 (18.10.2001)

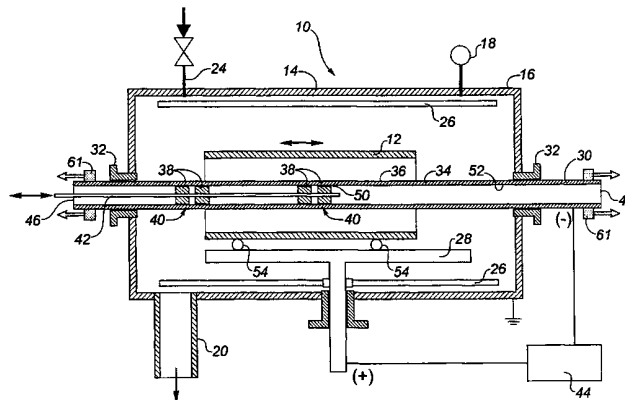
PCT

(10) International Publication Number
WO 01/77402 A3

- (51) International Patent Classification⁷: H01J 37/34 (74) Agent: MCKAY-CAREY, Mary, Jane; McKay-Carey & Company, Suite 2590 Commerce Place, 10155 - 102nd Street, Edmonton, Alberta T5J 4G8 (CA).
- (21) International Application Number: PCT/CA01/00413
- (22) International Filing Date: 30 March 2001 (30.03.2001) (81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
09/545,817 7 April 2000 (07.04.2000) US
- (71) Applicant (for all designated States except US): SURFACE ENGINEERED PRODUCTS CORPORATION [CA/CA]; 10102-114 Street, Fort Saskatchewan, Alberta T8L 3W4 (CA).
- (72) Inventors; and
(75) Inventors/Applicants (for US only): TZATZOV, Konstantin, K. [CA/CA]; 744 Wells Point Lane, Sherwood Park, Alberta T8A 4H8 (CA). GORODETSKY, Alexander, S. [CA/CA]; 521 Rainbow Crescent, Sherwood Park, Alberta T8A 5M8 (CA).
- (84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).
- Published:
— with international search report
- (88) Date of publication of the international search report:
28 March 2002

[Continued on next page]

(54) Title: METHOD AND APPARATUS FOR MAGNETRON SPUTTERING



WO 01/77402 A3

(57) Abstract: A cathode assembly for magnetron sputtering of a workpiece, and sputtering apparatus and methods of sputtering using same are provided. The cathode assembly includes a tubular cathode, which may be cylindrical in cross section along its length, or which may be curved or flexible, depending on the shape of workpiece that is to be sputtered, and which has a sputtering length of L_s . The cathode assembly also includes a magnet package, or a plurality of spaced magnet packages, each magnet package including either one magnet or a plurality of spaced magnets of alternating polarity, and having a magnet package length L_{pkg} which is less than L_s . The cathode assembly further includes one or more means for positioning, and preventing radial displacement of, the cathode along the axis of symmetry of the cathode. The magnet package is held within the cathode such that a driving force applied to the magnet package or to the cathode, or to both independently, imparts relative longitudinal movement between the magnet package and the cathode. The cathode assembly preferably includes cooling means. Furthermore, the magnet package(s) is preferably held within the cathode for shuttle movement. The cathode assembly allows for variations of one or more of the magnet package length, number, and spacing, and the relative displacement distance or shuttle distance, in order to tailor the erosion profile along the axis of symmetry of the cathode.



For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

INTERNATIONAL SEARCH REPORT

International Application No

PCT/CA 01/00413

A. CLASSIFICATION OF SUBJECT MATTER
IPC 7 H01J37/34

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

IPC 7 H01J C23C

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal, WPI Data, PAJ

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category °	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 4 221 652 A (KURIYAMA NOBORU) 9 September 1980 (1980-09-09) cited in the application	95,96, 115-117, 119, 123-125
A	column 3, line 14 -column 5, line 41 figures 3,6 --- -/--	1,19,41



Further documents are listed in the continuation of box C.



Patent family members are listed in annex.

° Special categories of cited documents :

- *A* document defining the general state of the art which is not considered to be of particular relevance
- *E* earlier document but published on or after the international filing date
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- *O* document referring to an oral disclosure, use, exhibition or other means
- *P* document published prior to the international filing date but later than the priority date claimed

- *T* later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention
- *X* document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone
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- * & * document member of the same patent family

Date of the actual completion of the international search

30 November 2001

Date of mailing of the international search report

06/12/2001

Name and mailing address of the ISA

European Patent Office, P.B. 5818 Patentlaan 2
NL - 2280 HV Rijswijk
Tel. (+31-70) 340-2040, Tx. 31 651 epo nl,
Fax: (+31-70) 340-3016

Authorized officer

Aguilar, M.

INTERNATIONAL SEARCH REPORT

International Application No
PCT/CA 01/00413

C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT		
Category	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	<p>WALKER S J ET AL: "Magnetron sputtering of solar coatings inside tubes" JOURNAL OF VACUUM SCIENCE AND TECHNOLOGY, NEW YORK, NY, US, vol. 19, no. 3, September 1981 (1981-09), pages 700-703, XP002139700 ISSN: 0022-5355 cited in the application page 700, paragraph 1 -page 701, paragraph 1 figure 1</p>	<p>95,96, 115-117, 119, 123-125</p>
A	<p>US 5 298 137 A (MARSHALL III JOHN) 29 March 1994 (1994-03-29) column 5, line 4 - line 28 column 10, line 11 - line 59 figures 1,8</p>	<p>1,19</p>
A	<p>US 5 301 211 A (BRYAN WILLIAM J ET AL) 5 April 1994 (1994-04-05) column 3, line 21 -column 4, line 28 figure 1</p>	<p>1,19</p>

INTERNATIONAL SEARCH REPORT

Information on patent family members

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